

CLASSIFICATION	
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U.S. UTILITY Patent Application

Serial No. 09/901657

Inventors: Tsuyoshi Nakamura, Taeko Ikegawa, Atsushi Sawano, Kousuke Doi

APPLICATION NO. 09/901657	CONT/PRIOR F	CLASS 430	SUBCLASS 270.1 322	ART UNIT 17562	EXAMINER BODA Young THORNTON
APPLICANTS Tsuyoshi Nakamura Taeko Ikegawa Atsushi Sawano Kousuke Doi					
TITLE Novel copolymer, photoresist composition, and process for forming resist pattern with high aspect ratio					

PTO-2040
12/99

INTERNATIONAL CLASSIFICATION	CLASS	SUBCLASS	ART UNIT

Continued on reverse side (See PTO Form 101)

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	(Assistant Examiner) _____ (Date) _____			NOTICE OF ALLOWANCE MAILED _____ (Date) _____	
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